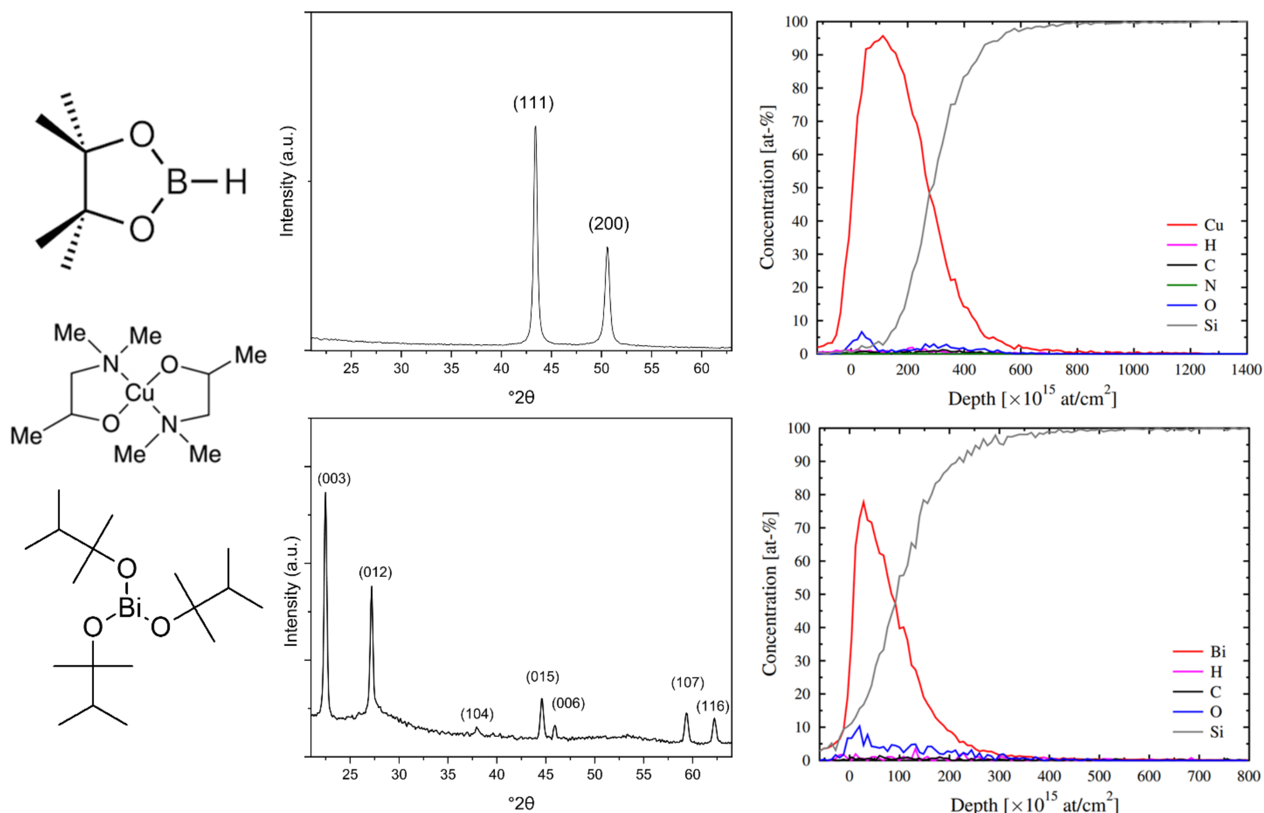

Figure 1. Left: Structures of the precursors used in this study. Top-middle: XRD diffractogram of Cu film deposited at 100 °C. Top-right: ToF-ERDA elemental depth profile of Cu film deposited at 100 °C. Bottom-middle: XRD diffractogram of Bi film deposited at 90 °C. Bottom-right: ToF-ERDA elemental depth profile of Bi film deposited at 90 °C.